

Resolution Plot

DESIGN MSX25-1000

Wafer No.: **3145-8**

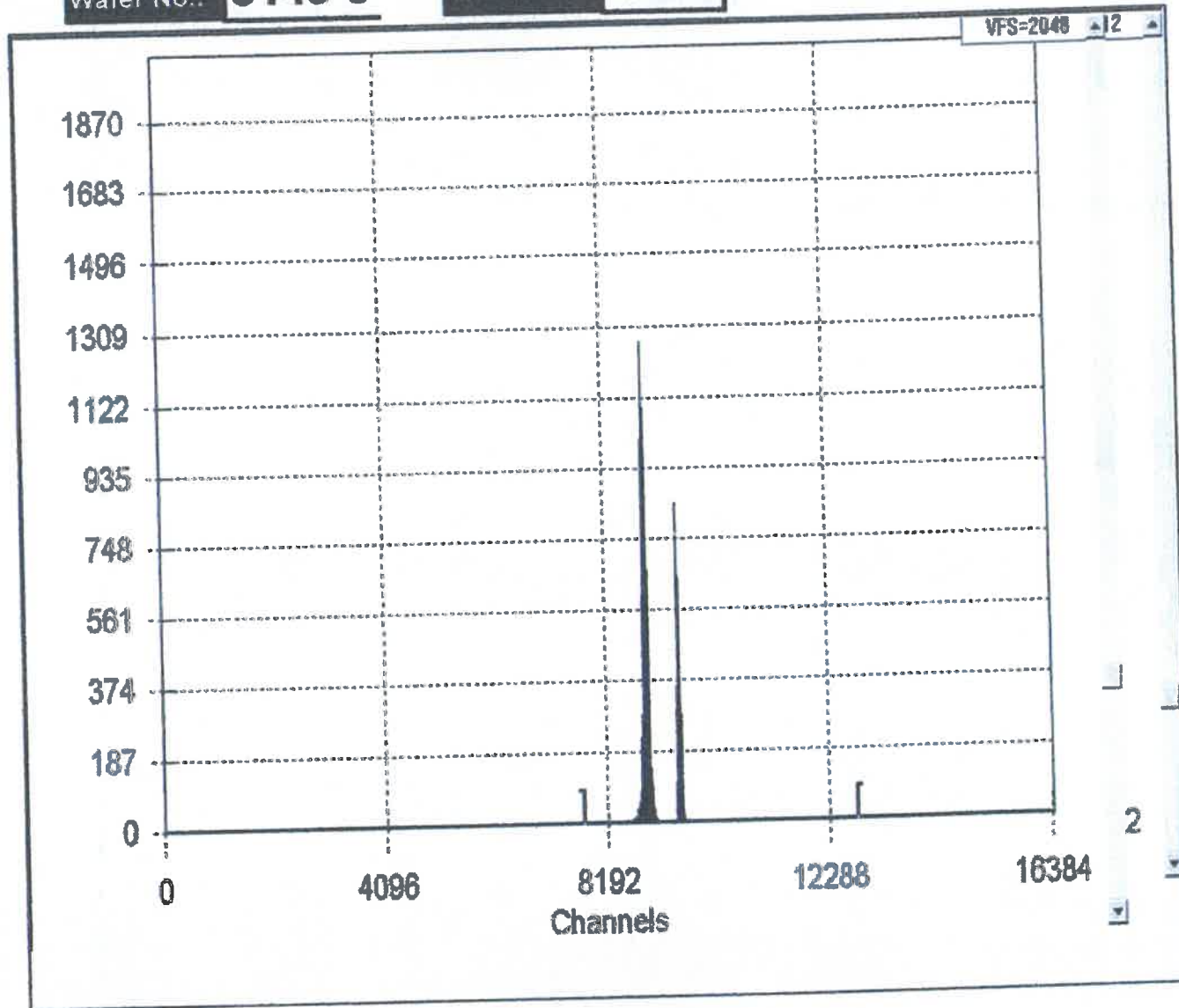
Thickness: **1029** μm

FUNCTION

DET LINE: **40.5** KeV
SYSTEM: **25.4** KeV
CAL: **31.5** KeV

OHMIC

DET LINE: **45.8** KeV
SYSTEM: **25.5** KeV
CALC: **38.1** KeV



Source

Am 241

Rise Time

1

Flat Top

0

T=22.2DC

BIAS VOLTS= **120** V

Leakage **184** nA

Micron Semiconductor
01/12/2014

CUSTOMER: STOCK
PURCHASE ORDER NUMBER:
DEVICE TYPE: MSX25-1000
DATE: 27/11/2014

MEASUREMENT DATA IN AIR:

TEMPERATURE: 22°C
HUMIDITY: 42%

DEVICE NUMBER	THICKNESS	OPERATING VOLTAGE	IR @ DEP.	IR @ DEP.+30V	VB @ 10uA	VF @ 10mA
3145-8	1029uM	175V	184nA	211nA	>200V	0.52V